TAIYO NIPPON SANSO The Gas Professionals

The Ultimate Gallium Nitride MOCVD System for High Quality Mass Production

UR25K

Evolution of Productivity Improvement For Power, High Frequency, and LED Devices

Advantages

- Based on the quality and uniformity-proven reactor of the atmospheric pressured SR series
- Automated parts handling system for the highest productivity
- Lowest cost of ownership by high growth rate epitaxy
- Highest throughput with the lowest downtime with Cl₂ dry cleaning equipment

UR25K Specifications

*General specifications are listed below.

Reactor type	Face up, rotation & revolution
Wafer size	4" × 10 or 6" × 7
Heating system	Multi zone resistance heater
Sources	TMGa, TEGa, TMAl, TMIn, NH ₃ , Cp ₂ Mg, SiH ₄
Gas nozzles	Three laminar flow horizontals
Transportation	Automatic susceptor unit transportation

*Options: Cassette-to-Cassette System

Applications

Epitaxial growth of GaN on Si (LED, Power device, etc.)

Process data (at atmospheric pressure)

XRD FWHM of un-GaN



PL peak wavelength mapping of MQW sample





0

Distance from wafer center [mm]

∕ = +0.91%

25

Reactor

Transportation system

Susceptor transport robot

Changing box

UR25K

Pass box

-25

TAIYO NIPPON SANSO Corporation

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